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**AMENDMENTS TO THE CLAIMS:**

1. (Currently Amended) A method of making a thin film explosive detonator, comprising:  
forming a substrate layer;  
depositing a metal layer of a metal in situ on the substrate layer; and  
reacting the metal layer ~~to form~~ for forming a primary explosive layer,  
wherein said primary explosive layer is comprised of an azide-based explosive salt with a predetermined thickness.
2. (Previously Presented) The method of claim 1, wherein the substrate layer comprises silicon.
3. (Previously Presented) The method of claim 1, wherein the metal layer comprises one of copper, nickel, cadmium, and silver.
4. (Previously Presented) The method of claim 1, wherein the metal layer is reacted with one of a gas phase reactant and a liquid phase reactant.
5. (Previously Presented) The method of claim 1, wherein said depositing a metal layer of a metal in situ on the substrate layer includes depositing the metal layer by at least one of plasma vapor deposition, chemical vapor deposition, electroplating, sputtering and sintering.
6. (Previously Presented) The method of claim 1, further comprising depositing an organic flyer layer on top of the primary explosive layer.
7. (Previously Presented) The method of claim 1, further comprising forming a barrel in the substrate layer.

8-16 (Cancelled)

17. (Cancelled)

18. (Previously Presented) The method of claim 1, wherein said explosive salt is comprised of one of copper azide, nickel azide, cadmium azides, silver azides, and fulminates.

19. (Previously Presented) The method of claim 1, wherein said primary explosive layer is comprised of copper azide with a predetermined thickness.

20. (Previously Presented) The method of claim 1, wherein said primary explosive layer is comprised of no more than about 10 milligrams of primary explosive.